

EasyTube® 2000

For synthesis of a wide variety of thin films and nanostructured materials

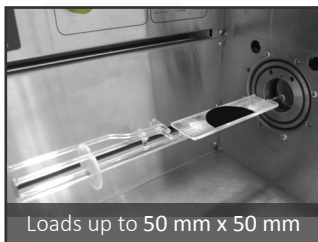


EasyTube® 2000 CVD system

The EasyTube® 2000 is an advanced turnkey chemical vapor deposition system for the synthesis of a wide variety of thin films and nanomaterials.

The base system can process 50 mm x 50 mm diameter substrates and has a 3-zone resistance heated furnace. The system is optimized for controlled process development and user safety. Our modular platform includes a range of options which can be configured to meet your specific processing requirements. Many of the options are available as upgrades after installation.

The system is designed to meet today's safety standards for handling pyrophoric, corrosive, flammable, and toxic gases such as hydrogen, silane, germane, diborane, hydrogen chloride, and metal organic precursors.



Loads up to 50 mm x 50 mm



Clamshell FastCool™ Furnace



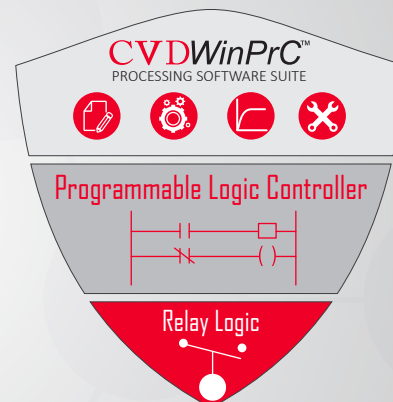
Optional EasyExhaust Burn Box

powered by **CVDWinPrC™**

Operated through our CVDWinPrC™ process control software, the system automatically logs data and graphically shows time-dependent values of user-selected parameters. CVDWinPrC™ also allows users to load preprogrammed recipes, modify, check and create new recipes, and view realtime or saved process data.

Safety Protocols

The system has application configured safety protocols embedded into relay logic, PLC, and CVDWinPrC™ software.



Standard Features

- CVDWinPrC™ system control software for realtime process control, data logging, and recipe editing
- Preprogrammed process recipes
- Substrate sizes up to 50 mm x 50 mm
- Cantilevered automatic substrate loading/unloading system
- Up to 8 mass flow-controlled UHP gas lines
- Atmospheric and/or low pressure process configurations available
- 3-zone resistance furnace for temperatures up to 1200 °C or optional rapid thermal processing with infrared heater
- Proprietary realtime cascade process temperature control
- High throughput with FastCool™ furnace
- User ability to set warnings and alarms
- Comprehensive software and hardware safety interlocks
- 1 year warranty
- On-site system startup and training
- Semi - S2/S8 and CE Compliant

Options

- High temperature resistance furnace up to > 1200 °C
- Infrared heating for rapid thermal processing > 1100 °C
- DC bias field-assisted growth
- Rectangular process tube for improved laminar gas flow
- Up to an additional 4 mass flow-controlled UHP gas lines
- Liquid/solid source vapor delivery kit
- Bubbler liquid auto refill
- Run/vent: stabilizes gas flows (bypassing the process tube) before flowing into process tube
- Residual gas analyzer
- Air to water heat exchanger for cooling water
- EasyGas™ hazardous gas cabinets
- EasyPanel™ gas panels for argon, nitrogen, helium, oxygen
- EasyExhaust™ exhaust gas conditioning system (scrubber/pyrolyzer)
- Gas purification
- NRTL certification

Facility Requirements

Dimensions*	64" Length	30" Width	60" Height
Electrical*	208 VAC / 60 Hz	L1, L2, L3, Neutral, Ground	30 - 40 Amps
Cooling Water*	1 GPM	10 - 50 PSIG	75 °F Max
Pneumatic Supply	1 SCFM	80 PSIG	Clean Air or Nitrogen
Facility Nitrogen*	10 SLPM	20 PSIG	
Cabinet Exhaust*	300 SCFM	1" WC	
Process Gases	Customer specified		

*Note:

Electrical requirements vary by Country | Facility requirements vary with system options | Consult factory for details

FirstNano® offers CVD processing systems with support equipment such as gas cabinets and exhaust gas conditioning systems. All major components from one vendor makes component interfacing easy.

Call us at **+1 631-981-7081** to discuss a product solution for your project.
We can also be reached at **sales@firstnano.com** or visit our website.

CVD
Equipment
Corporation

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